WO 2004/066360 PCT/US2004/001798

CLAIMS

We claim:

1. A coil assembly, comprising:

at least one coil;

- at least one boss coupled to the at least one coil, wherein the at least one boss comprises at least two support sections.
 - 2. The coil assembly of claim 1, wherein the coil comprises a metal or a metal alloy.
 - 3. The coil assembly of claim 2, wherein the metal or metal alloy comprises a transition metal.
- 10 4. The coil assembly of claim 3, wherein the transition metal comprises tantalum or titanium.
 - 5. The coil assembly of claim 1, wherein the at least one boss comprises more than 3 bosses.
- 6. The coil assembly of claim 5, wherein the at least one boss comprises more than 5 bosses.
 - 7. The coil assembly of claim 1, wherein the at least one boss comprises the same material as the coil.
 - 8. The coil assembly of claim 1, wherein the at least one boss is coupled to the coil through a welded joint.
- 20 9. The coil assembly of claim 8, wherein the welded joint is formed by laser welding or e-beam welding.
 - 10. The coil assembly of claim 1, wherein the at least one boss is molded to the coil as one continuous piece of material.
- The coil assembly of claim 1, wherein the at least one boss comprises a first support section and a second support section and wherein the diameter of the first support section is different from the diameter of the second support section.
 - 12. An ion depositing apparatus comprising the coil assembly of claim 1.

WO 2004/066360 PCT/US2004/001798

13. A sputtering chamber assembly comprising the ion depositing apparatus of claim 12.

- 14. A sputtering chamber assembly comprising the coil assembly of claim 1.
- 15. The coil assembly of claim 1, wherein the assembly comprises a heat transfer device.
- 16. The coil assembly of claim 15, wherein the heat transfer device comprises the at least one boss.
 - 17. The coil assembly of claim 15, wherein the heat transfer device comprises the at least one boss and the coil.
 - 18. The coil assembly of claim 1, wherein the coil comprises a thickness of less than about 0.2 inches.
- 10 19. The coil assembly of claim 18, wherein the coil comprises a thickness of less than about 0.13 inches.
 - 20. A method of producing a coil assembly, comprises:

 providing a coil;

 providing at least one boss having at least two support sections; and
- coupling the at least one boss to the coil.
 - 21. The method of claim 20, wherein the coil comprises a metal or a metal alloy.
 - 22. The method of claim 21, wherein the metal or metal alloy comprises a transition metal.
- 23. The method of claim 22, wherein the transition metal comprises tantalum or titanium.
 - 24. The method of claim 20, wherein the at least one boss comprises more than 3 bosses.
 - 25. The method of claim 24, wherein the at least one boss comprises more than 5 bosses.
- 25 26. The method of claim 20, wherein the at least one boss comprises the same material as the coil.

WO 2004/066360 PCT/US2004/001798

27. The method of claim 20, wherein the at least one boss is coupled to the coil through a welded joint.

- 28. The method of claim 27, wherein the welded joint is formed by laser welding or ebeam welding.
- 5 29. The method of claim 20, wherein the at least one boss is molded to the coil as one continuous piece of material.
 - 30. The method of claim 20, wherein the at least one boss comprises a first support section and a second support section and wherein the diameter of the first support section is different from the diameter of the second support section.
- 10 31. An ion depositing apparatus comprising the coil assembly produced by the method of claim 20.
 - 32. A sputtering chamber assembly comprising the ion depositing apparatus of claim 31.
 - 33. A sputtering chamber assembly comprising the coil assembly produced by the method of claim 20.
- 15 34. The method of claim 20, wherein the assembly comprises a heat transfer device.
 - 35. The method of claim 34, wherein the heat transfer device comprises the at least one boss.
 - 36. The method of claim 34, wherein the heat transfer device comprises the at least one boss and the coil.
- The method of claim 20, wherein the coil comprises a thickness of less than about 0.2 inches.
 - 38. The method of claim 37, wherein the coil comprises a thickness of less than about 0.13 inches.